

=> d his

(FILE 'HOME' ENTERED AT 17:59:41 ON 20 MAY 2003)

FILE 'REGISTRY' ENTERED AT 17:59:56 ON 20 MAY 2003

L1 SCREEN 964 AND 970 AND 1015 AND 1051
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 0 S L3 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:00:24 ON 20 MAY 2003

L5 0 S L4

FILE 'REGISTRY' ENTERED AT 18:00:51 ON 20 MAY 2003

L6 SCREEN 964 AND 970 AND 1015 AND 1051 AND 2067
L7 STRUCTURE UPLOADED
L8 QUE L7 AND L6
L9 0 S L8 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:01:15 ON 20 MAY 2003

L10 0 S L9

FILE 'REGISTRY' ENTERED AT 18:01:25 ON 20 MAY 2003

L11 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYLADAMANTINE
L12 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYL ADAMANTINE
L13 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYL ADAMANTANE
L14 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYLADAMANTANE

FILE 'HOME' ENTERED AT 18:03:18 ON 20 MAY 2003

FILE 'REGISTRY' ENTERED AT 18:07:37 ON 20 MAY 2003

L15 SCREEN 970 AND 2067
L16 STRUCTURE UPLOADED
L17 QUE L16 AND L15
L18 5 S L17 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:08:32 ON 20 MAY 2003

L19 17 S L18
L20 8 DUPLICATE REMOVE L19 (9 DUPLICATES REMOVED)

FILE 'HOME' ENTERED AT 18:09:19 ON 20 MAY 2003

FILE 'REGISTRY' ENTERED AT 18:10:06 ON 20 MAY 2003

L21 SCREEN 970 AND 2076 AND 2067
L22 STRUCTURE UPLOADED
L23 QUE L22 AND L21
L24 0 S L23

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:10:45 ON 20 MAY 2003

L25 0 S L24

FILE 'HOME' ENTERED AT 18:10:54 ON 20 MAY 2003

FILE 'REGISTRY' ENTERED AT 18:13:10 ON 20 MAY 2003

L26 SCREEN 970 AND 2067
L27 STRUCTURE UPLOADED
L28 QUE L27 AND L26
L29 0 S L28 SSS SAM

STN-CAS
SEARCH
DO NOT REMOVE

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:13:35 ON 20 MAY
2003

L30

0 S L29

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 970 AND 2067

L15 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\09463059.str

L16 STRUCTURE UPLOADED

=> que L16 AND L15

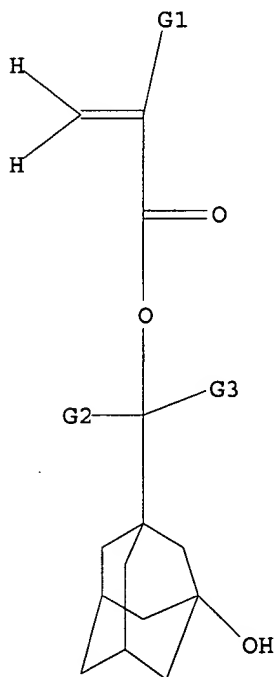
L17 QUE L16 AND L15

=> d

L17 HAS NO ANSWERS

L15 SCR 970 AND 2067

L16 STR



G1 Me,H

G2 H,Ak,Cy

G3 Cy,Ak

Structure attributes must be viewed using STN Express query preparation.

L17 QUE ABB=ON PLU=ON L16 AND L15

=> s l17 sss sam

SAMPLE SEARCH INITIATED 18:08:17 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 7 TO ITERATE

100.0% PROCESSED 7 ITERATIONS

5 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 7 TO 298
PROJECTED ANSWERS: 5 TO 234

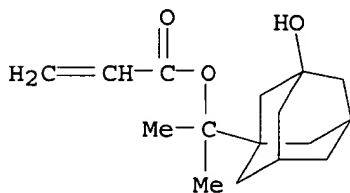
L18 5 SEA SSS SAM L16 AND L15

=> d

L18 ANSWER 1 OF 5 REGISTRY COPYRIGHT 2003 ACS
RN 450410-08-9 REGISTRY
CN 2-Propenoic acid, 3,5-dihydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer
with 1-(3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl 2-propenoate
(9CI) (CA INDEX NAME)
MF (C16 H24 O3 . C13 H18 O4)x
CI PMS
PCT Polyacrylic
SR CA
LC STN Files: CA, CAPLUS, USPATFULL

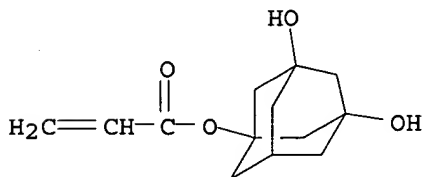
CM 1

CRN 262608-27-5
CMF C16 H24 O3



CM 2

CRN 216581-85-0
CMF C13 H18 O4



1 REFERENCES IN FILE CA (1957 TO DATE)
1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

2.48

143.18

FILE 'CAPLUS' ENTERED AT 18:08:32 ON 20 MAY 2003

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
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FILE 'HCAPLUS' ENTERED AT 18:08:32 ON 20 MAY 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 18:08:32 ON 20 MAY 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPAT2' ENTERED AT 18:08:32 ON 20 MAY 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> d his

(FILE 'HOME' ENTERED AT 17:59:41 ON 20 MAY 2003)

FILE 'REGISTRY' ENTERED AT 17:59:56 ON 20 MAY 2003

L1 SCREEN 964 AND 970 AND 1015 AND 1051
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
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FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:00:24 ON 20 MAY 2003

L5 0 S L4

FILE 'REGISTRY' ENTERED AT 18:00:51 ON 20 MAY 2003

L6 SCREEN 964 AND 970 AND 1015 AND 1051 AND 2067
L7 STRUCTURE UPLOADED
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L9 0 S L8 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:01:15 ON 20 MAY 2003

L10 0 S L9

FILE 'REGISTRY' ENTERED AT 18:01:25 ON 20 MAY 2003

L11 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYLADAMANTINE
L12 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYL ADAMANTINE
L13 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYL ADAMANTANE
L14 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYLADAMANTANE

FILE 'HOME' ENTERED AT 18:03:18 ON 20 MAY 2003

FILE 'REGISTRY' ENTERED AT 18:07:37 ON 20 MAY 2003

L15 SCREEN 970 AND 2067
L16 STRUCTURE UPLOADED
L17 QUE L16 AND L15
L18 5 S L17 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:08:32 ON 20 MAY 2003

=> s l18

L19 17 L18

=> duplicates remove

ENTER L# LIST OR (END):l19

DUPLICATE PREFERENCE IS 'CAPLUS, HCAPLUS, USPATFULL'

KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n

PROCESSING COMPLETED FOR L19

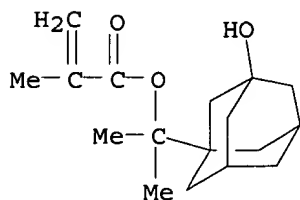
L20 8 DUPLICATE REMOVE L19 (9 DUPLICATES REMOVED)

=> d 120 1-8 ibib hitstr

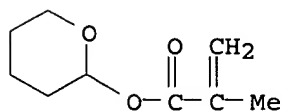
L20 ANSWER 1 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 1
ACCESSION NUMBER: 2002:654986 CAPLUS
DOCUMENT NUMBER: 137:192769
TITLE: Polymeric compound and resin composition for photoresist
INVENTOR(S): Ushirogouchi, Toru; Okino, Takeshi; Asakawa, Koji; Shida, Naomi; Funaki, Yoshinori; Tsutsumi, Kiyoharu; Takaragi, Akira; Inoue, Keizo
PATENT ASSIGNEE(S): Kabushiki Kaisha Toshiba, Japan; Daicel Chemical Industries, Ltd.
SOURCE: U.S., 24 pp.
CODEN: USXXAM
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 6440636	B1	20020827	US 2000-703677	20001102
PRIORITY APPLN. INFO.:			US 2000-703677	20001102

IT 338790-67-3P 450410-08-9P
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polymeric compd. and resin compn. for photoresist)
RN 338790-67-3 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2H-pyran-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)
CM 1
CRN 324761-49-1
CMF C17 H26 O3



CM 2
CRN 52858-59-0
CMF C9 H14 O3



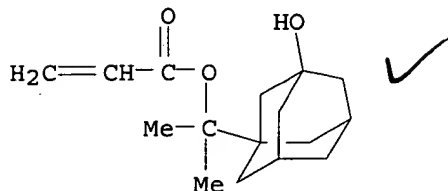
RN 450410-08-9 CAPLUS
CN 2-Propenoic acid, 3,5-dihydroxytricyclo[3.3.1.1.3,7]dec-1-yl ester, polymer with 1-(3-hydroxytricyclo[3.3.1.1.3,7]dec-1-yl)-1-methylethyl 2-propenoate

(9CI) (CA INDEX NAME)

CM 1

CRN 262608-27-5

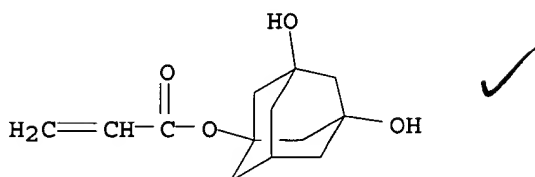
CMF C16 H24 O3



CM 2

CRN 216581-85-0

CMF C13 H18 O4



REFERENCE COUNT: 13 THERE ARE 13 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L20 ANSWER 2 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 2
ACCESSION NUMBER: 2002:292089 CAPLUS
DOCUMENT NUMBER: 136:316934
TITLE: Positive-working photoresist composition for fabrication of semiconductor device
INVENTOR(S): Sato, Kenichiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 51 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

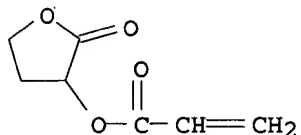
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002116544	A2	20020419	JP 2000-310761	20001011
PRIORITY APPLN. INFO.:			JP 2000-310761	20001011
OTHER SOURCE(S):	MARPAT 136:316934			
IT	412015-88-4			

RL: TEM (Technical or engineered material use); USES (Uses)
(pos.-working photoresist compn. for fabrication of semiconductor device)

RN 412015-88-4 CAPLUS

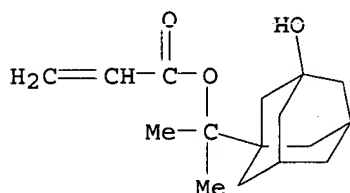
CN 2-Propenoic acid, 1-(3-hydroxytricyclo[3.3.1.1.3,7]dec-1-yl)-1-methylethyl ester, polymer with 2,5-furandione, 1,2,3,4,4a,5,8,8a-octahydro-1,4:5,8-dimethanonaphthalene and tetrahydro-2-oxo-3-furanyl 2-propenoate (9CI)
(CA INDEX NAME)

CRN 328249-37-2
CMF C7 H8 O4



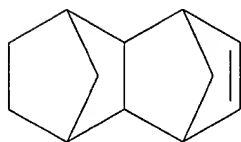
CM 2

CRN 262608-27-5
CMF C16 H24 O3



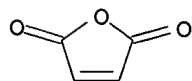
CM 3

CRN 21635-90-5
CMF C12 H16



CM 4

CRN 108-31-6
CMF C4 H2 O3



L20 ANSWER 3 OF 8 CAPLUS COPYRIGHT 2003 ACS

DUPLICATE 3

ACCESSION NUMBER: 2001:347119 CAPLUS

DOCUMENT NUMBER: 134:346475

TITLE: Adamantyl-containing polymer for photoresist and polymer composition for photoresist

INVENTOR(S) : Gokochi, Toru; Okino, Takeshi; Asakawa, Koji; Shinoda,
Naomi; Funaki, Katsunori; Tsutsumi, Kiyoharu; Horai,

Akira; Inoue, Keizo
 PATENT ASSIGNEE(S): Toshiba Corp., Japan; Daicel Chemical Industries, Ltd.
 SOURCE: Jpn. Kokai Tokkyo Koho, 23 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

5/15/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001131232	A2	20010515	JP 1999-312329	19991102
PRIORITY APPLN. INFO.:			JP 1999-312329	19991102

11-2-99

IT 338790-67-3P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (adamantyl-contg. polymer for etching-resistant photoresist for semiconductor device fabrication)

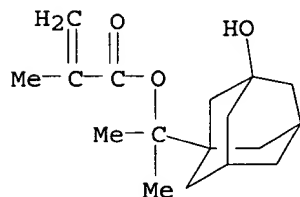
RN 338790-67-3 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2H-pyran-2-yl
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 324761-49-1

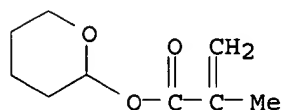
CMF C17 H26 O3



CM 2

CRN 52858-59-0

CMF C9 H14 O3



L20 ANSWER 4 OF 8 CAPLUS COPYRIGHT 2003 ACS

DUPLICATE 4

ACCESSION NUMBER: 2001:117245 CAPLUS

DOCUMENT NUMBER: 134:170832

TITLE: Positive-working photoresist composition suitable for exposed with ArF excimer laser

INVENTOR(S): Sato, Kenichiro; Shirakawa, Hiroshi; Aogo, Toshiaki

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 48 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

2/16/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001042535	A2	20010216	JP 1999-211370	19990726
PRIORITY APPLN. INFO.:			JP 1999-211370	19990726

IT 324761-53-7P 324761-58-2P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(alicyclic polymer in pos.-working photoresist compn.)

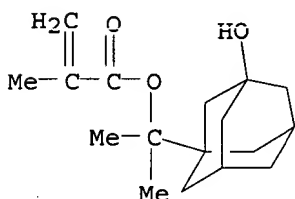
RN 324761-53-7 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 324761-49-1

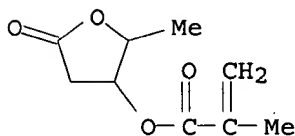
CMF C17 H26 O3



CM 2

CRN 324761-23-1

CMF C9 H12 O4



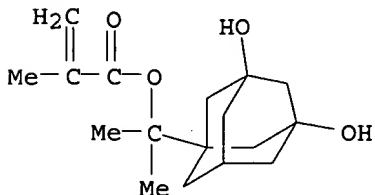
RN 324761-58-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

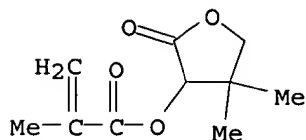
CM 1

CRN 324761-57-1

CMF C17 H26 O4



CRN 156938-13-5
CMF C10 H14 O4



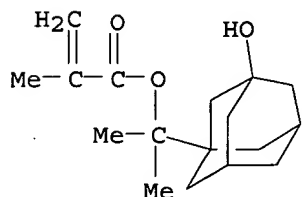
L20 ANSWER 5 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 5
ACCESSION NUMBER: 2001:117244 CAPLUS
DOCUMENT NUMBER: 134:170858
TITLE: Positive-working photoresist composition suitable for
exposed with ArF excimer laser
INVENTOR(S): Sato, Kenichiro; Shirakawa, Hiroshi; Aogo, Toshiaki
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 48 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION: 1/10/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2001042534	A2	20010216	JP 1999-211369	19990726
PRIORITY APPLN. INFO.:			JP 1999-211369	19990726

IT 324761-53-7P 324761-58-2P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(alicyclic polymer in pos.-working photoresist compn.)
RN 324761-53-7 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

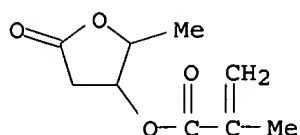
CM 1

CRN 324761-49-1
CMF C17 H26 O3



CM 2

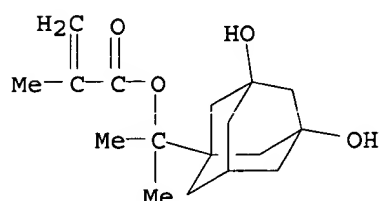
CRN 324761-23-1
CMF C9 H12 O4



RN 324761-58-2 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.1.3,7]dec-1-yl)-
 1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

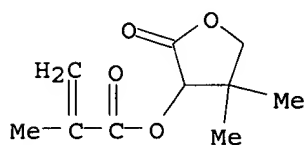
CM 1

CRN 324761-57-1
 CMF C17 H26 O4



CM 2

CRN 156938-13-5
 CMF C10 H14 O4



L20 ANSWER 6 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 6
 ACCESSION NUMBER: 2001:117243 CAPLUS
 DOCUMENT NUMBER: 134:170831
 TITLE: Positive-working photoresist composition suitable for
 exposed with ArF excimer laser
 INVENTOR(S): Sato, Kenichiro; Shirakawa, Hiroshi; Aogo, Toshiaki
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 47 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

2/16/01

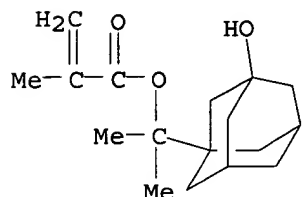
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JP 2001042533	A2	20010216	JP 1999-211368	19990726
PRIORITY APPLN. INFO.:			JP 1999-211368	19990726

IT 324761-53-7P. 324761-58-2P
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material
 use); PREP (Preparation); USES (Uses)
 (alicyclic polymer in pos.-working photoresist compn.)

RN 324761-53-7 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

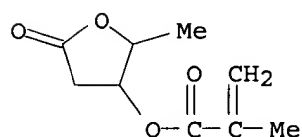
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CRN 324761-49-1
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CM 2

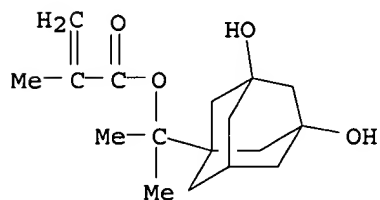
CRN 324761-23-1
 CMF C9 H12 O4



RN 324761-58-2 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

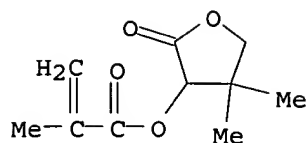
CM 1

CRN 324761-57-1
 CMF C17 H26 O4



CM 2

CRN 156938-13-5
 CMF C10 H14 O4



L20 ANSWER 7 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 7
 ACCESSION NUMBER: 2001:117242 CAPLUS
 DOCUMENT NUMBER: 134:170830
 TITLE: Positive-working photoresist composition suitable for exposed with ArF excimer laser
 INVENTOR(S): Sato, Kenichiro; Shirakawa, Hiroshi; Aogo, Toshiaki
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 47 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

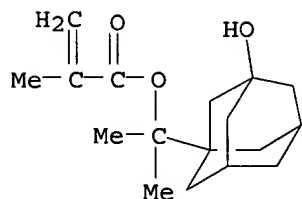
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001042532	A2	20010216	JP 1999-211367	19990726
PRIORITY APPLN. INFO.:			JP 1999-211367	19990726

IT 324761-53-7P 324761-58-2P
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (alicyclic polymer in pos.-working photoresist compn.)
 RN 324761-53-7 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 324761-49-1

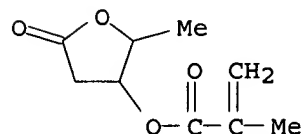
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CRN 324761-23-1

CMF C9 H12 O4

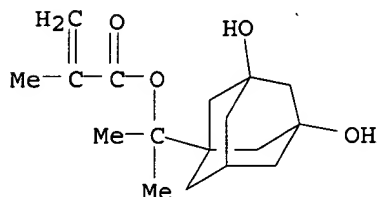


RN 324761-58-2 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 324761-57-1

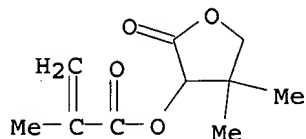
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CM 2

CRN 156938-13-5

CMF C10 H14 O4



L20 ANSWER 8 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 8
ACCESSION NUMBER: 2001:98658 CAPLUS
DOCUMENT NUMBER: 134:170817
TITLE: Positive-working photoresist composition for exposure to far ultraviolet light
INVENTOR(S): Sato, Kenichiro; Kodama, Kunihiro; Aogo, Toshiaki
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 47 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

2/9/01

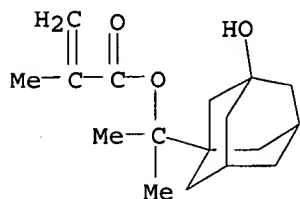
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001033969	A2	20010209	JP 1999-203676	19990716
PRIORITY APPLN. INFO.: JP 1999-203676				19990716

IT 324761-53-7P 324761-58-2P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(pos.-working photoresist compn. contg. polymer with alicyclic group for exposure to far UV light)

RN 324761-53-7 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

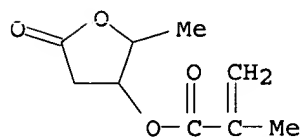
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CMF C17 H26 O3



CM 2

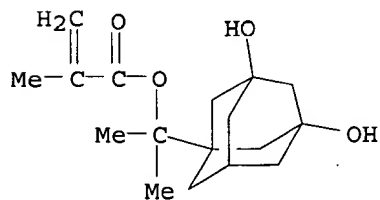
CRN 324761-23-1
CMF C9 H12 O4



RN 324761-58-2 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.1.3,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

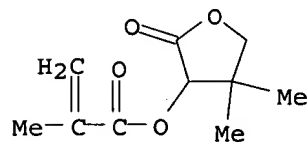
CM 1

CRN 324761-57-1
CMF C17 H26 O4



CM 2

CRN 156938-13-5
CMF C10 H14 O4



Patent Assignment Abstract of Title

Total Assignments: 2

Application #: 09703677 **Filing Dt:** 11/02/2000 **Patent #:** 6440636 **Issue Dt:** 08/27/2002

PCT #: NONE

Publication #: NONE

Pub Dt:

Inventors: Toru Ushirogouchi, Takeshi Okino, Koji Asakawa, Naomi Shida, Yoshinori Funaki, Kiyoharu Tsutsumi, Akira Takaragi, Keizo Inoue

Title: POLYMERIC COMPOUND AND RESIN COMPOSITION FOR PHOTORESIST

Assignment: 1

Reel/Frame: 011434/0499 **Received:** 01/22/2001 **Recorded:** 11/02/2000 **Mailed:** 03/29/2001 **Pages:** 3

Conveyance: ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS).

Assignors: USHIROGOUCHI, TORU

Exec Dt: 10/23/2000

OKINO, TAKESHI

Exec Dt: 10/23/2000

ASAKAWA, KOJI

Exec Dt: 10/23/2000

SHIDA, NAOMI

Exec Dt: 10/23/2000

Assignee: KABUSHIKI KAISHA TOSHIBA

72 HORIKAWA-CHO, SAIWAI-KU

KAWASAKI-SHI KANAGAWA-KEN, JAPAN

Correspondent: BIRCH, STEWART, KOLASCH & BIRCH, LLP

RAYMOND C. STEWART

P.O. BOX 747

FALLS CHURCH, VA 22040-0747

Assignment: 2

Reel/Frame: 011434/0506 **Received:** 01/22/2001 **Recorded:** 11/02/2000 **Mailed:** 03/29/2001 **Pages:** 3

Conveyance: ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS).

Assignors: FUNAKI, YOSHINORI

Exec Dt: 10/23/2000

TSUTSUMI, KIYOHARU

Exec Dt: 10/23/2000

TAKARAGI, AKIRA

Exec Dt: 10/23/2000

INOUE, KEIZO

Exec Dt: 10/23/2000

Assignee: DAICEL CHEMICAL INDUSTRIES, LTD.

1, TEPPU-CHO, SAKAI-SHI

OSAKA, JAPAN

Correspondent: BIRCH STEWART KOLASCH ET AL

RAYMOND C. STEWART

P.O. BOX 747

FALLS CHURCH, VIRGINIA 22040-0747

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Patent Assignment Abstract of Title

Total Assignments: 1

Application #: 09463059

Filing Dt: 01/19/2000

Patent #: NONE

Issue Dt:

PCT #: NONE

Publication #: NONE

Pub Dt:

Inventor: TATSUYA NAKANO

Title: ACID-SENSITIVE COMPOUND AND RESIN COMPOSITION FOR PHOTORESIST

Assignment: 1

Reel/Frame: 010634/0922

Received:

03/29/2000

Recorded:

01/19/2000

Mailed:

06/05/2000

Pages: 3

Conveyance: ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS).

Assignor: NAKANO, TATSUYA

Exec Dt: 01/08/2000

Assignee: DAICEL CHEMICAL INDUSTRIES, LTD.

1, TEPPU-CHO, SAKAI-SHI

OSAKA 590-8501, JAPAN

Correspondent: BIRCH, STEWART, KOLASCH & BIRCH, LLP

RAYMOND C. STEWART

P.O. BOX 747

FALLS CHURCH, VA 22040-0747

Search Results as of: 5/20/2003 6:28:02 P.M.

If you have any comments or questions concerning the data displayed, contact OPR / Assignments at 703-308-9723
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